

The New XUV Optics Beamline at BESSY-II



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**Institute for Nanometre Optics
and Technology, BESSY-II**

The new Optics Beamline at BESSY II

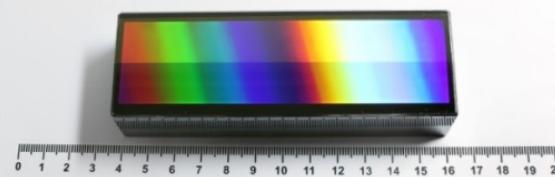
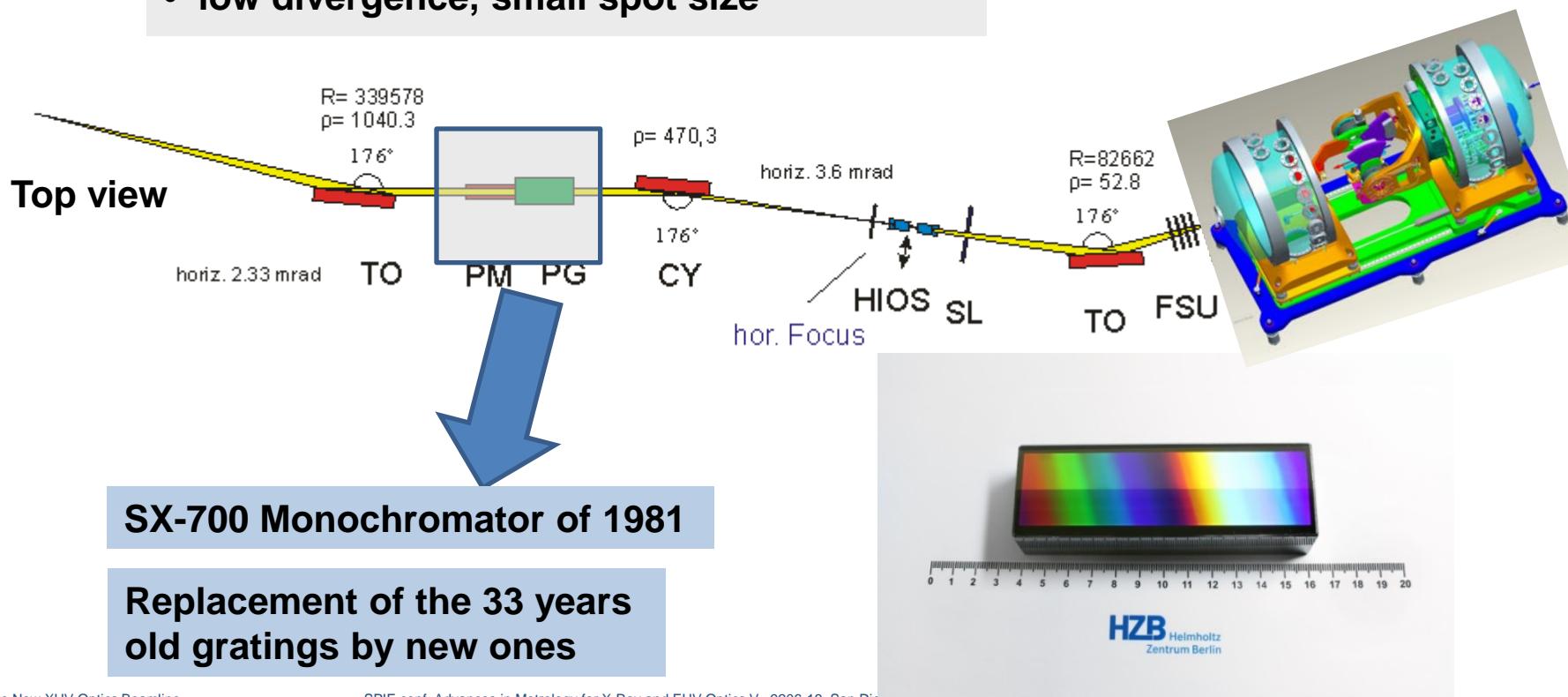
Characterisation of in-house produced gratings and more

Collimated PGM

- 10 - 2000 eV
- moderate resolution 10.000 (@500 eV)
- polarization linear/elliptical
- higher order light suppression
- low divergence, small spot size

Reflectometry

- „at-wavelength“ metrology
- quality control
- in-house R&D
- user operation
- short-term access

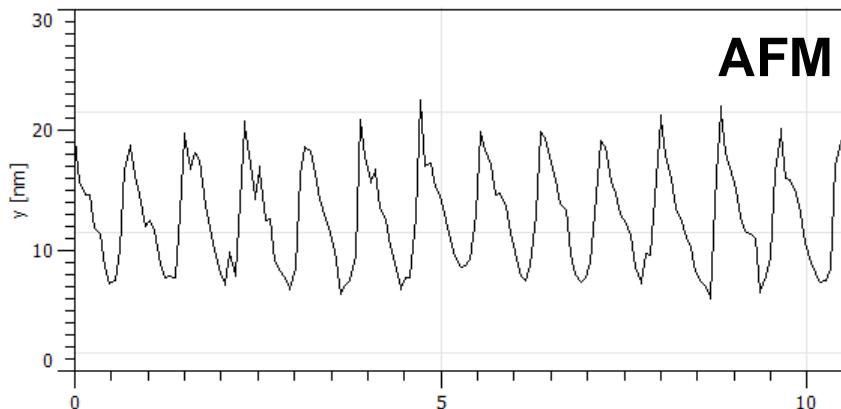


HZB
Helmholtz
Zentrum Berlin

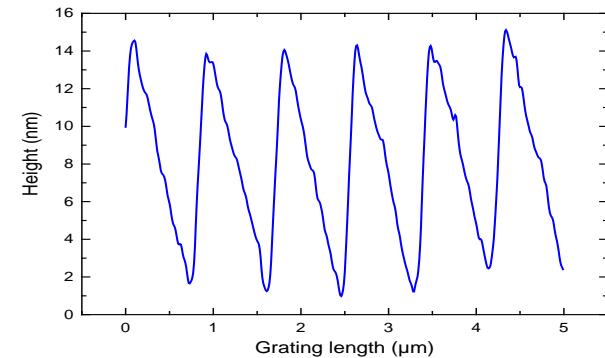


Grating performance

old grating 1200 l/mm

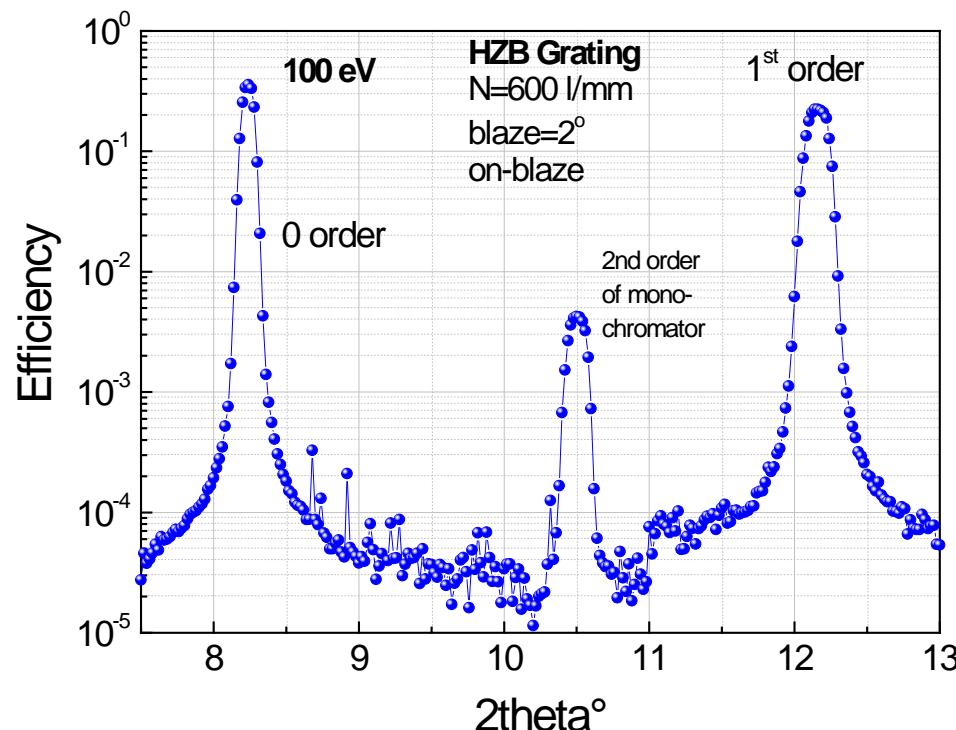


new HZB-grating 1200 l/mm

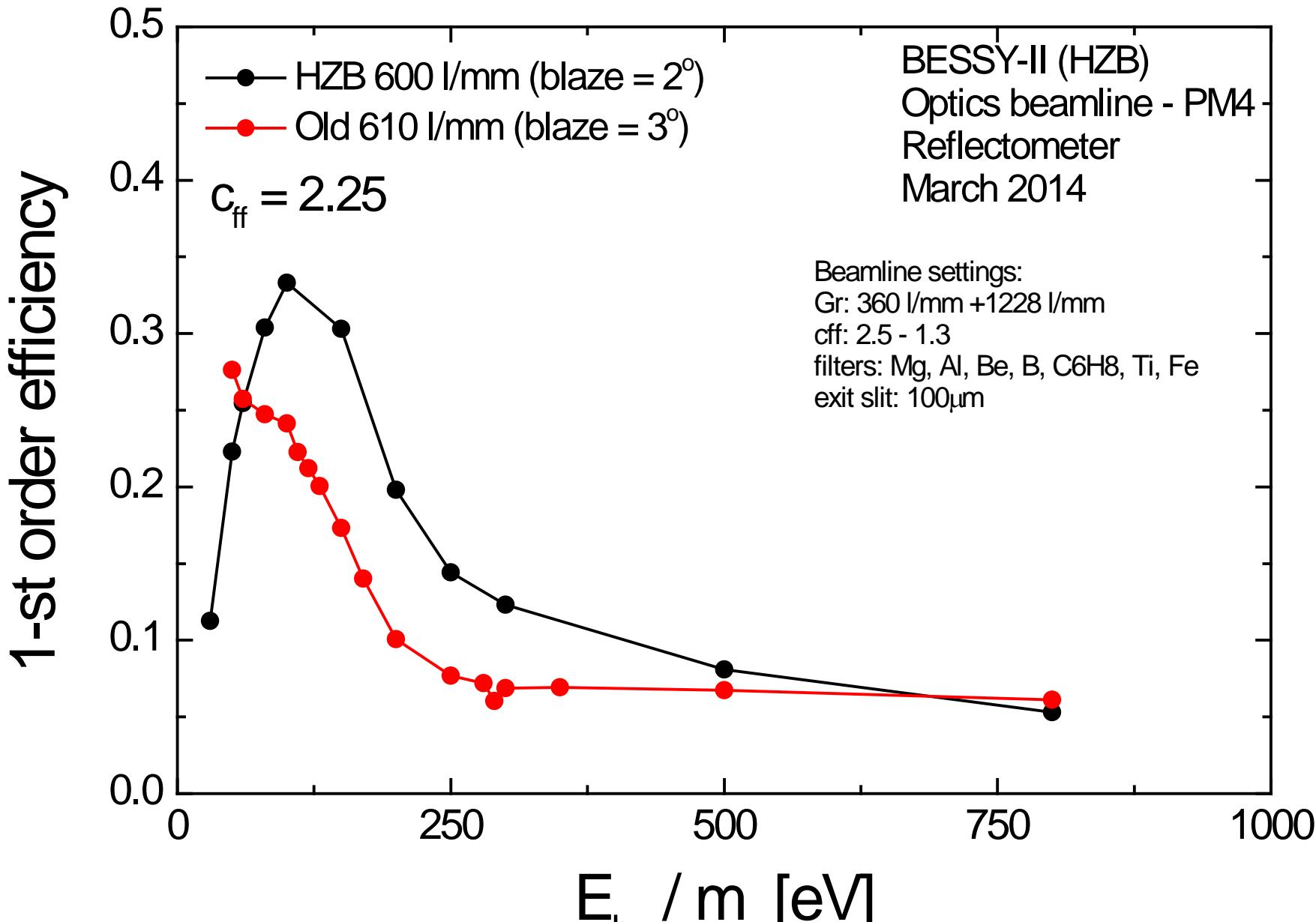


$\Theta_{\text{blaze}} = 1.1^\circ$

$\sigma = 0.3 \text{ nm rms}$

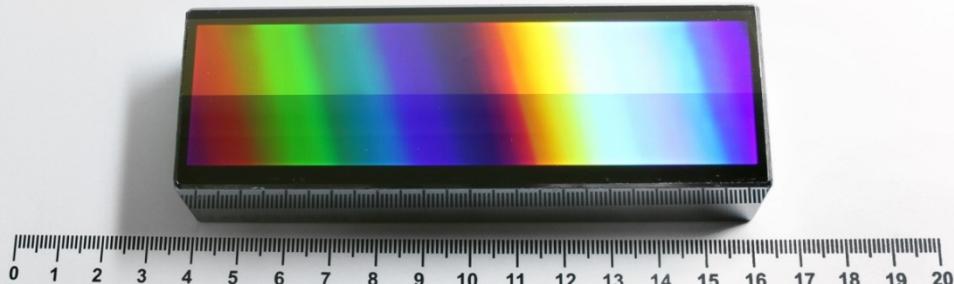


600 l/mm – old / new



Metrology on a blazed grating: efficiency

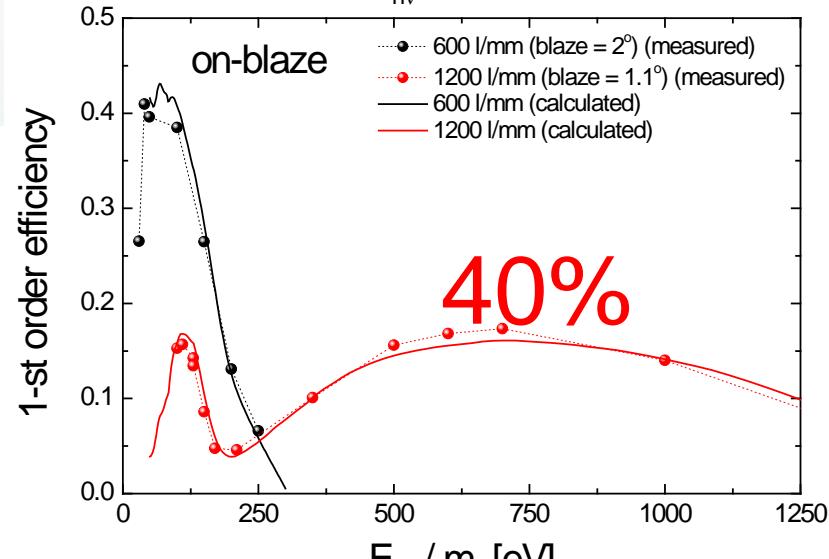
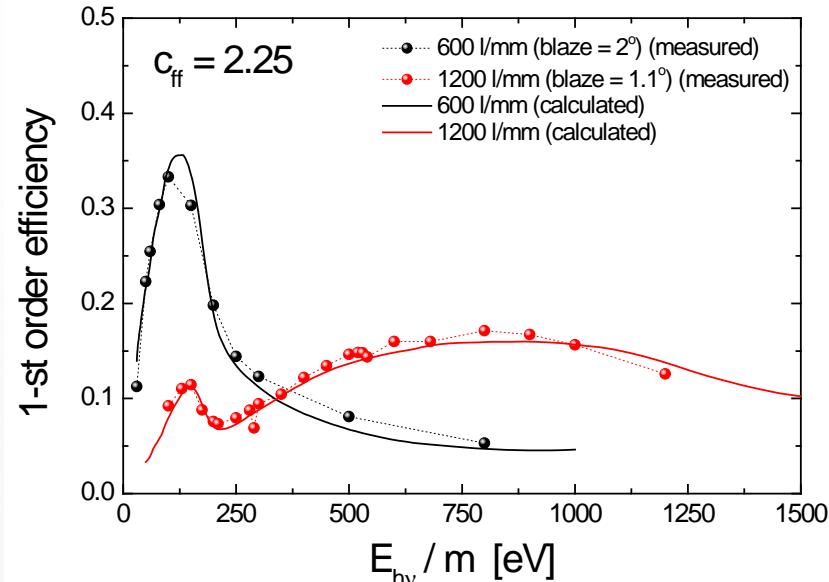
Technology Center for Precision Optical Gratings (HZB)



HZB Helmholtz
Zentrum Berlin

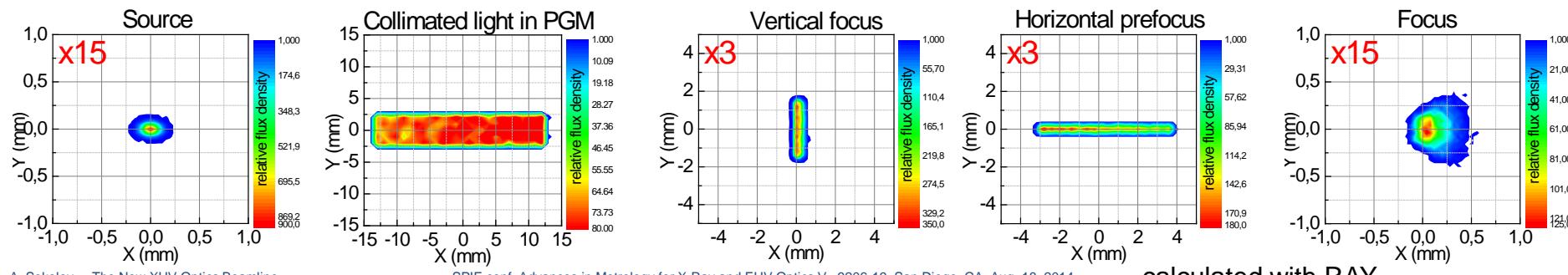
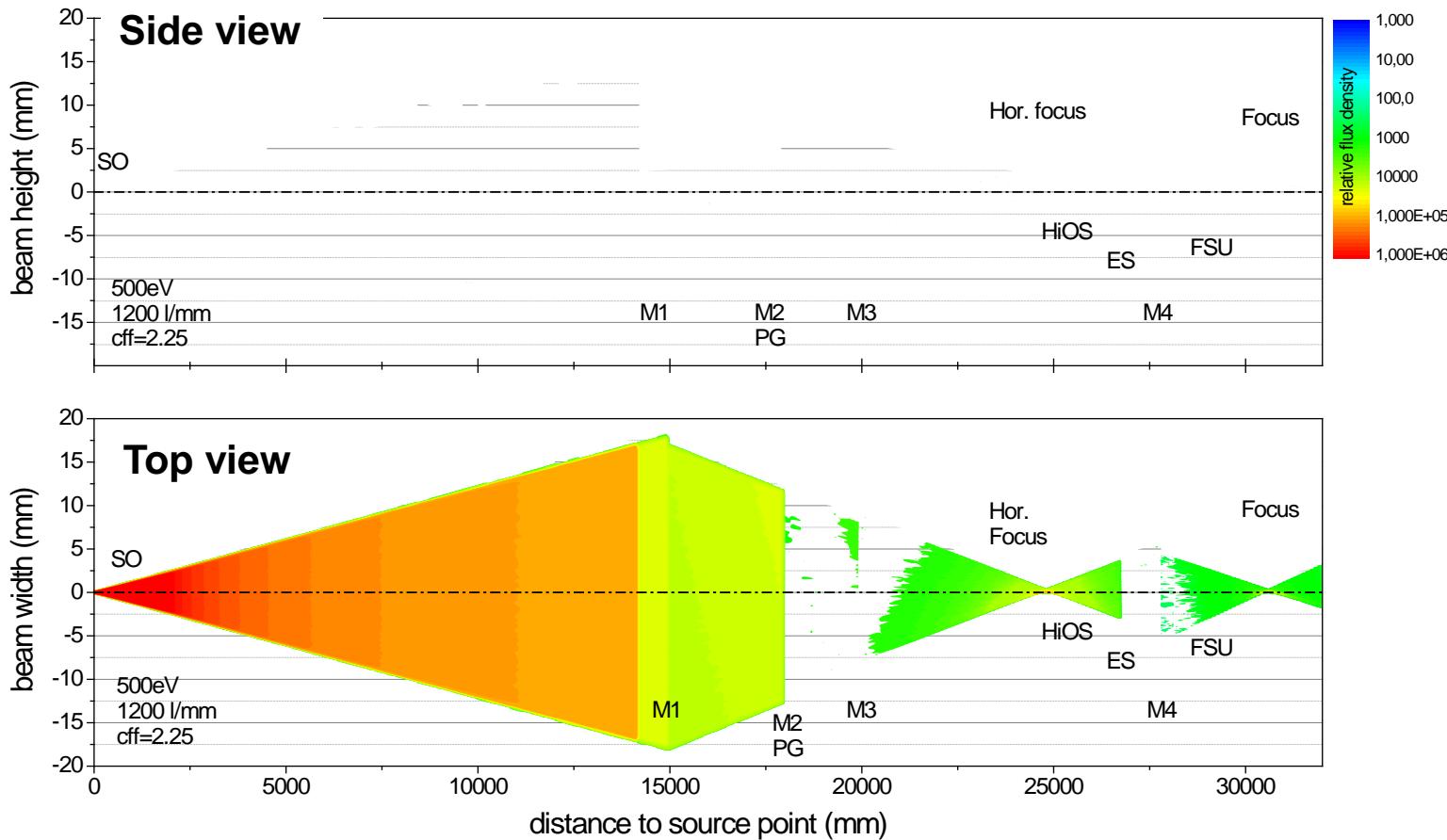
Line density	600 l/mm	1200 l/mm
Blaze angle	2.0°	1.1°
σ rms	0.6 nm	0.3 nm
Au-Coating	40 nm	40 nm

- HZB-grating production is well established now

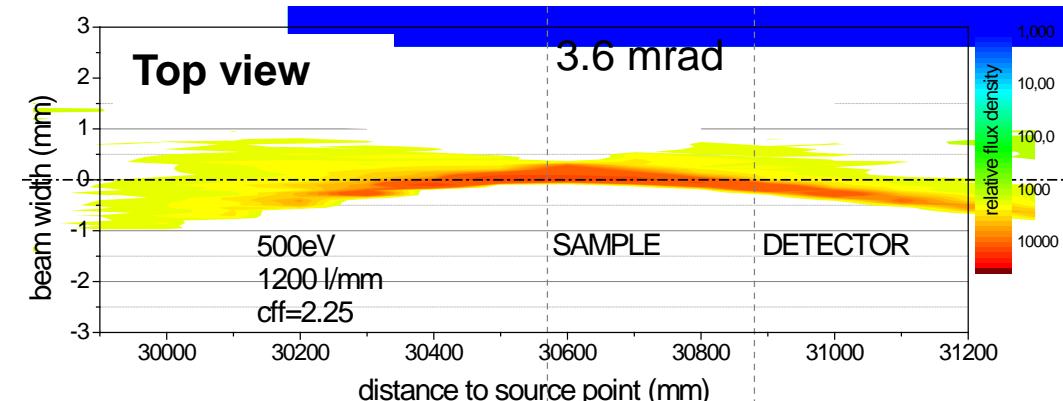
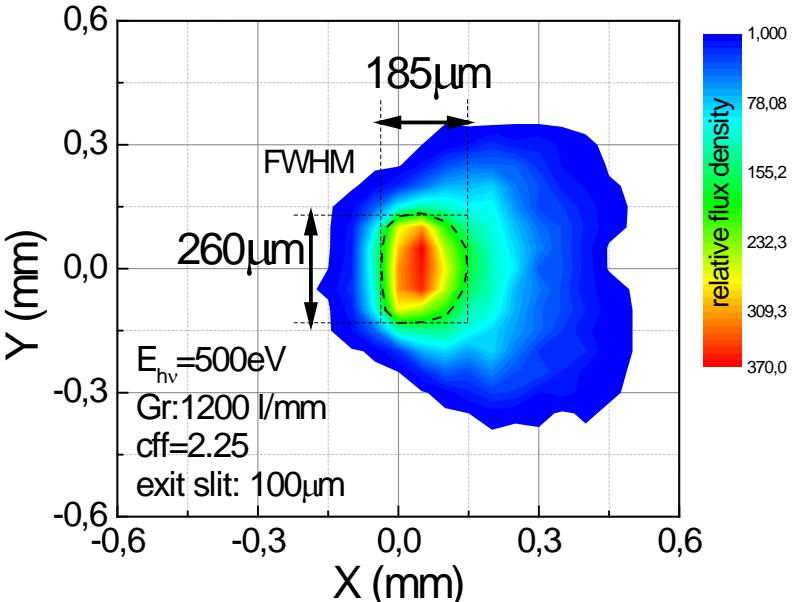
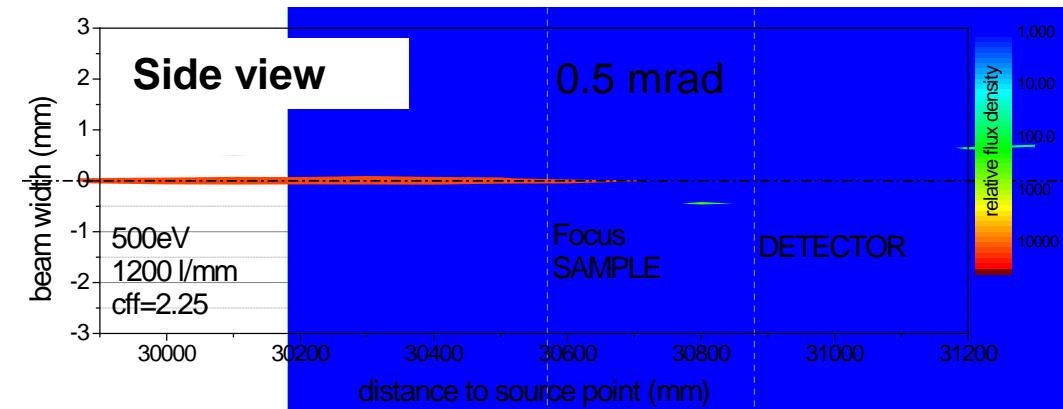


- gratings are better than old ones (blazeangle, roughness, efficiency, straylight)

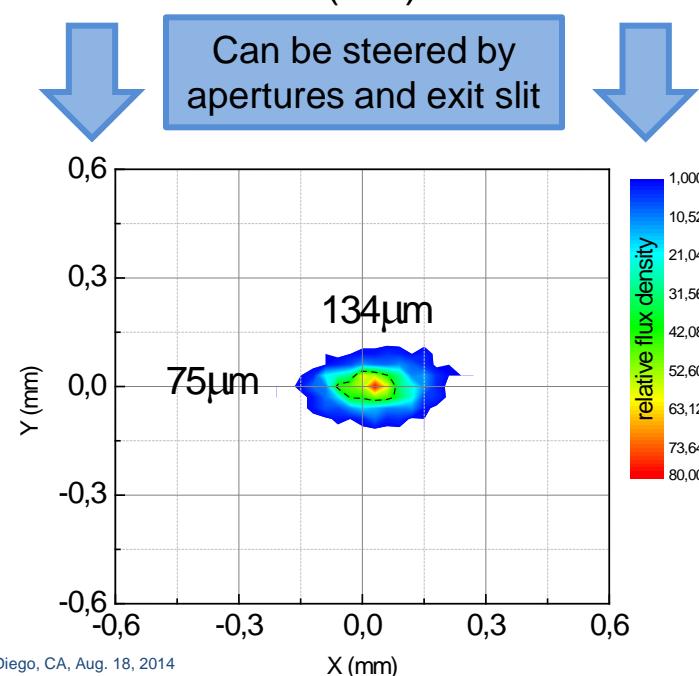
Beam size and divergence



Beam size and divergence at the sample



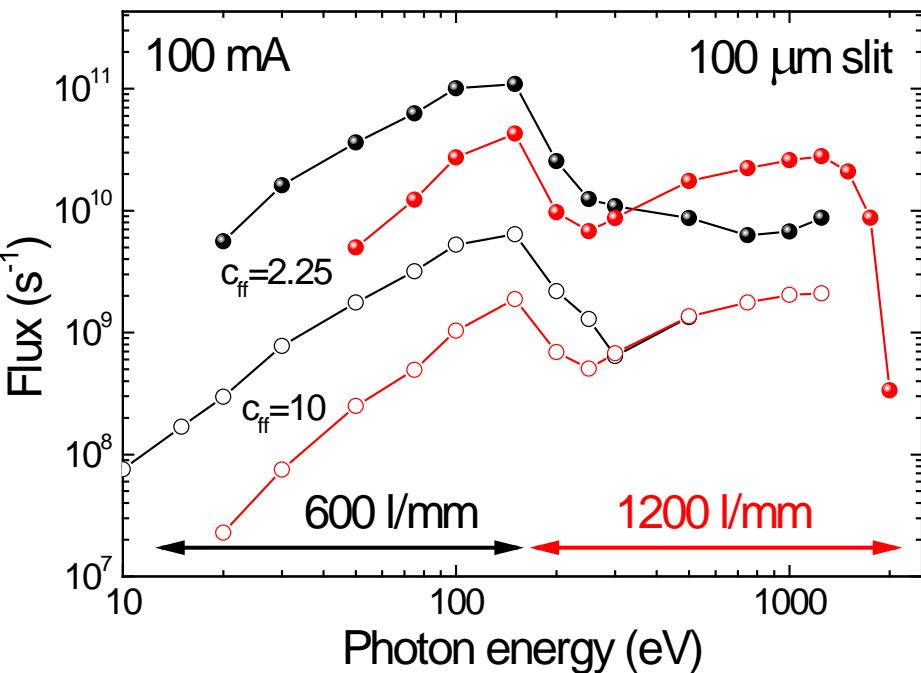
calculated with RAY



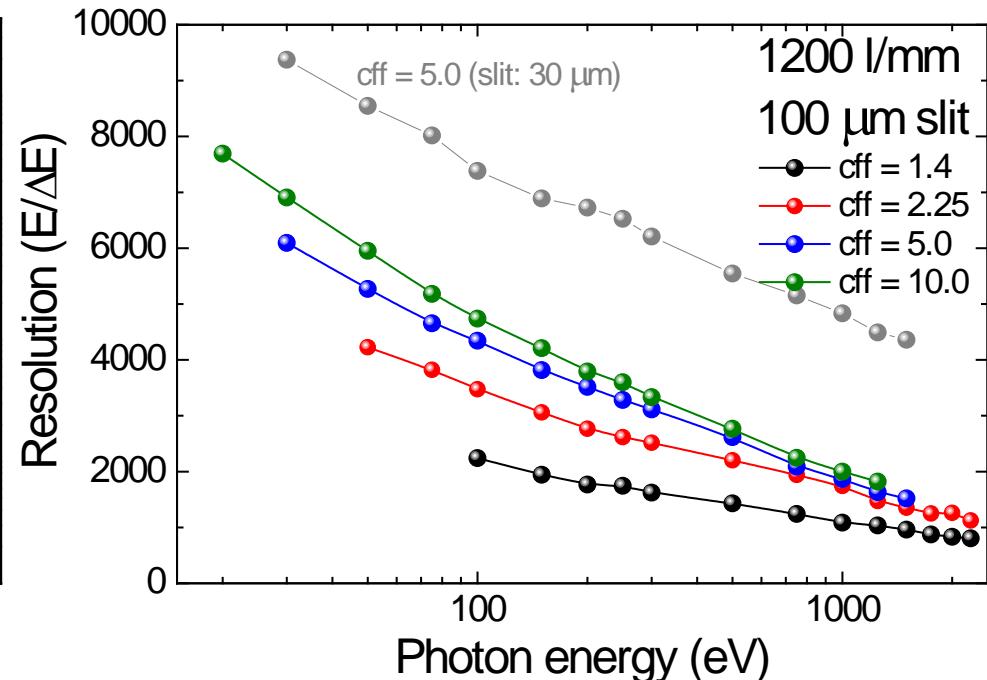
Can be steered by apertures and exit slit

Flux and resolution

$10^{10} - 10^{11}$ photons/s/100 mA

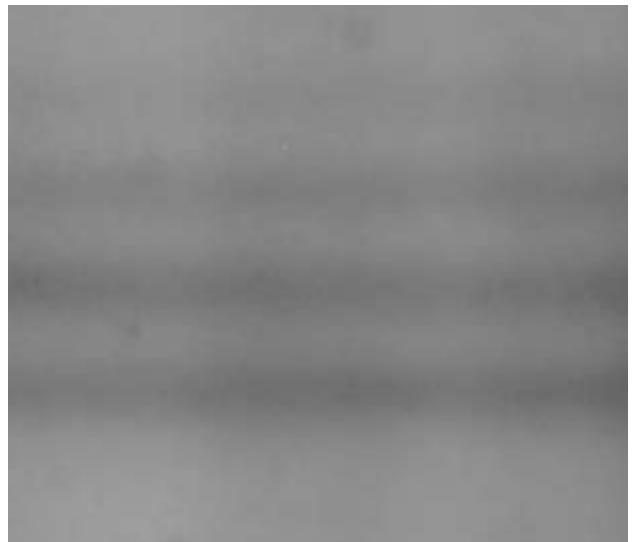
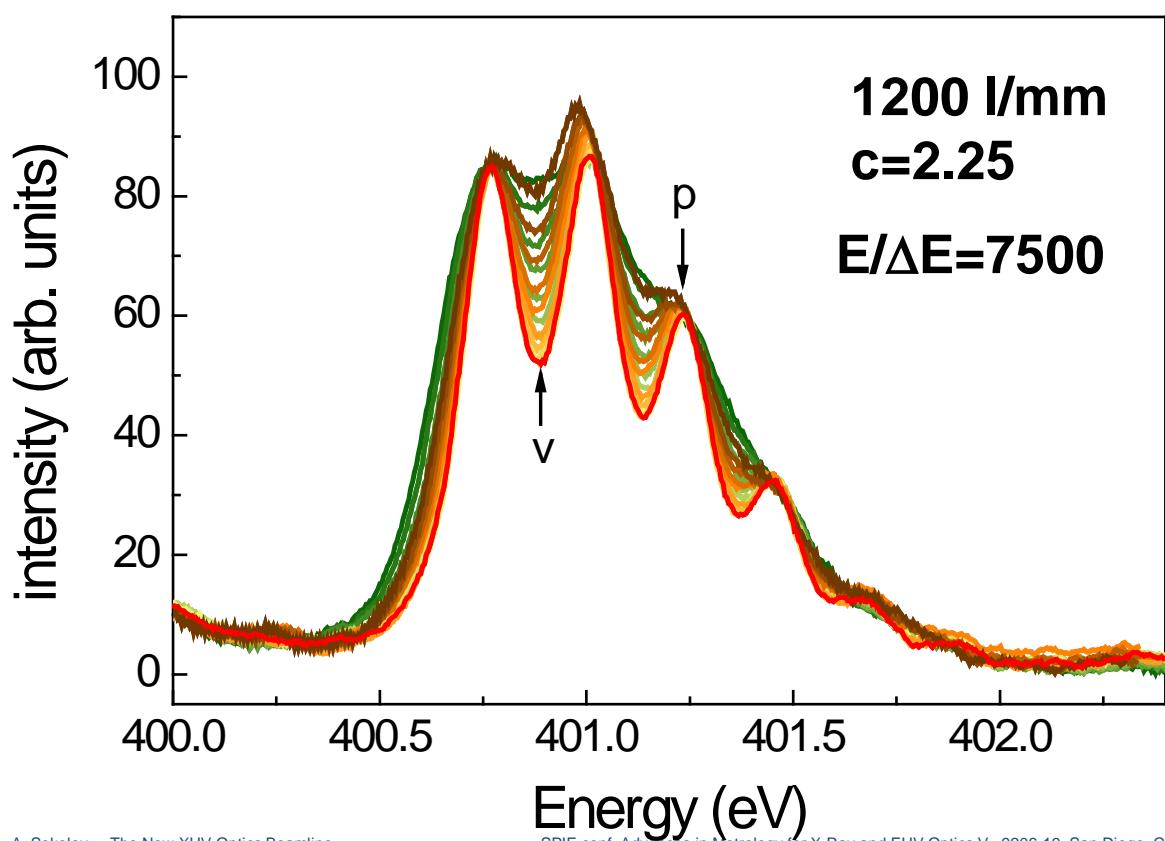
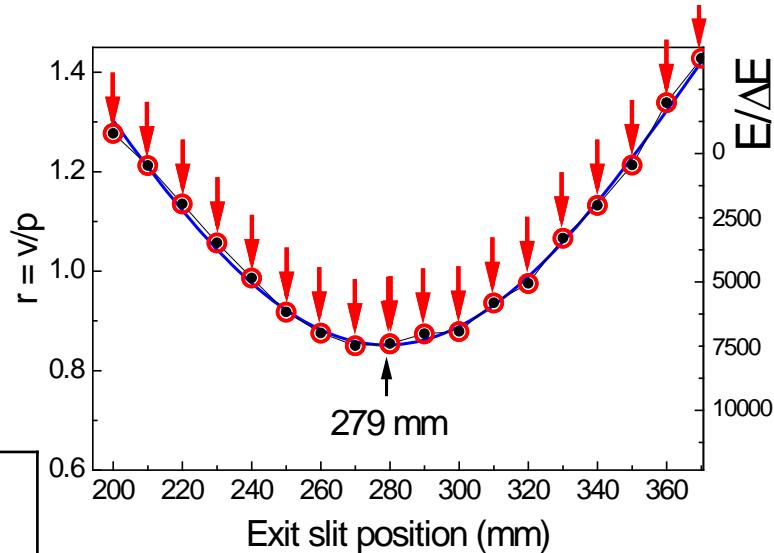


$E/\Delta E = 1.000 - 10.000$



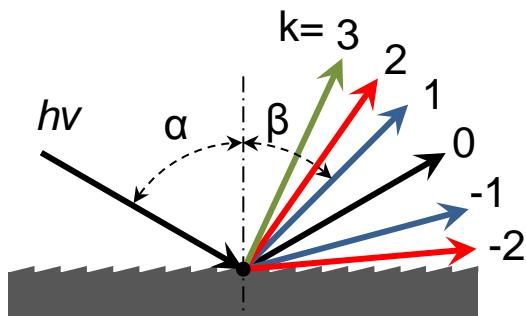
Calculations with RAY

Energy resolution @ Nitrogen k-edge



The famous c-factor

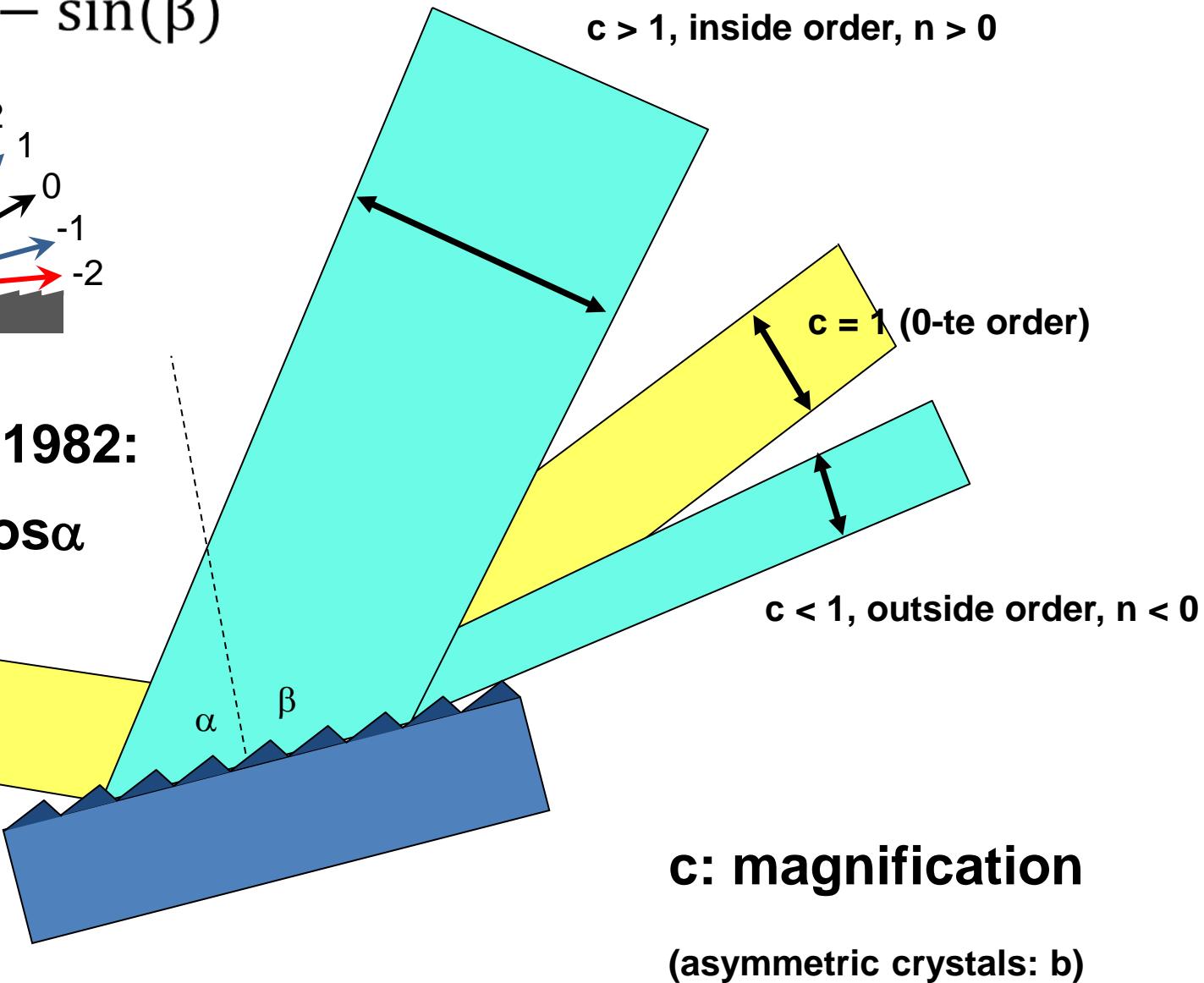
$$Nk\lambda = \sin(\alpha) - \sin(\beta)$$



$c > 1$, inside order, $n > 0$

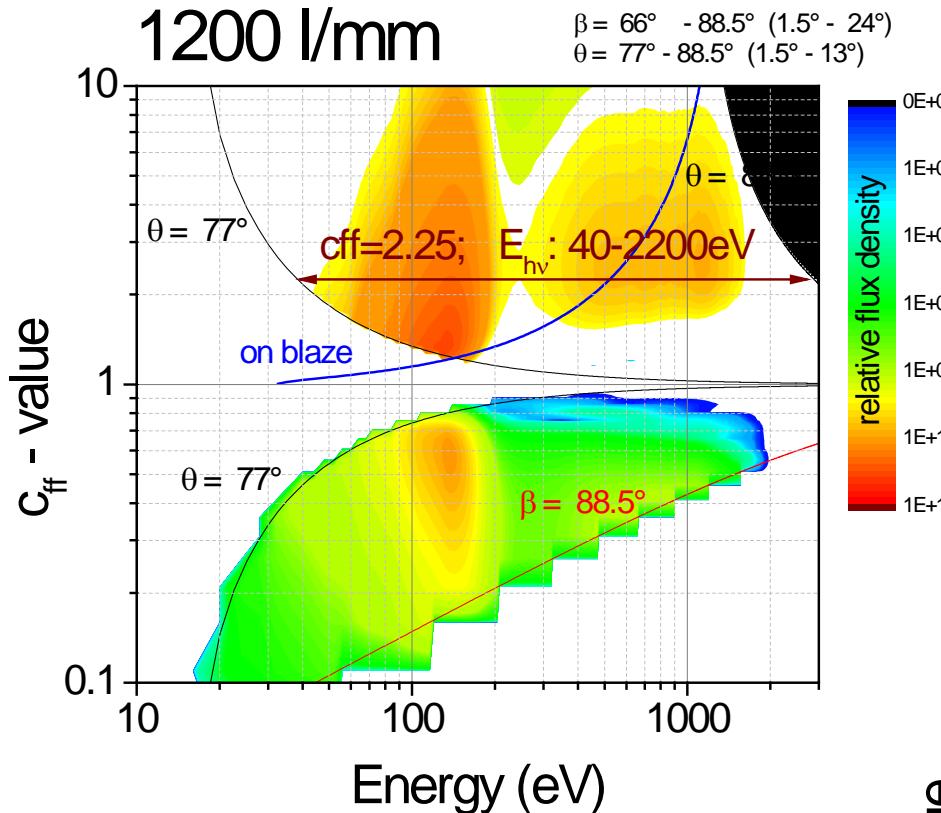
H. Petersen 1982:

$$c_{ff} = \cos\beta / \cos\alpha$$



Working energy range

1200 l/mm



Wide energy range:
10 eV – 2200 eV

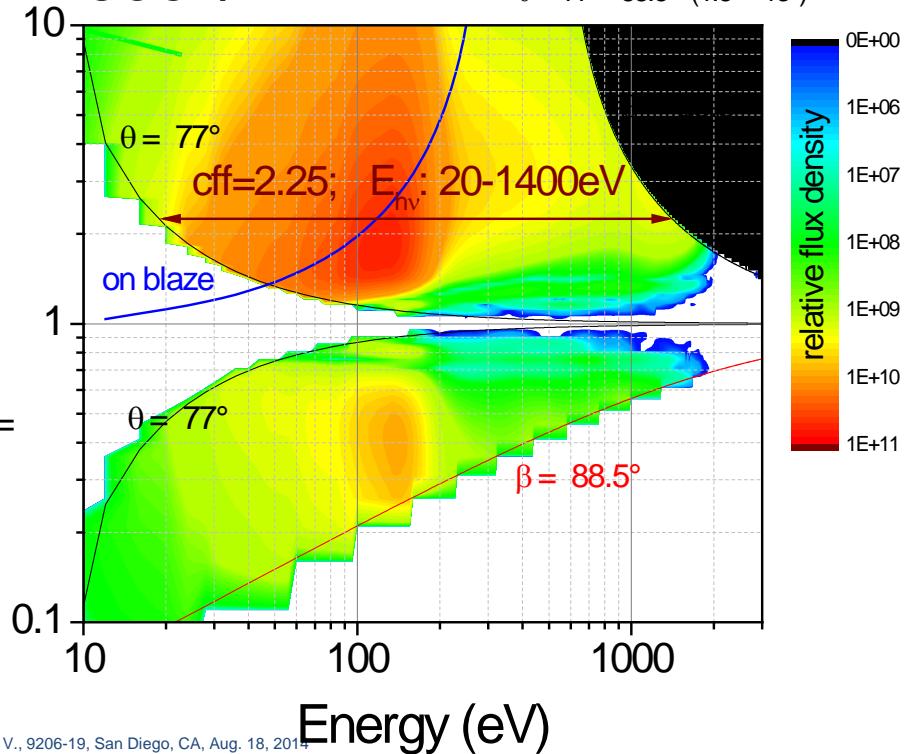
Calculations with REFLEC

SX700 ZEISS monochromator

Gratings: **1200 l/mm** and **600 l/mm**

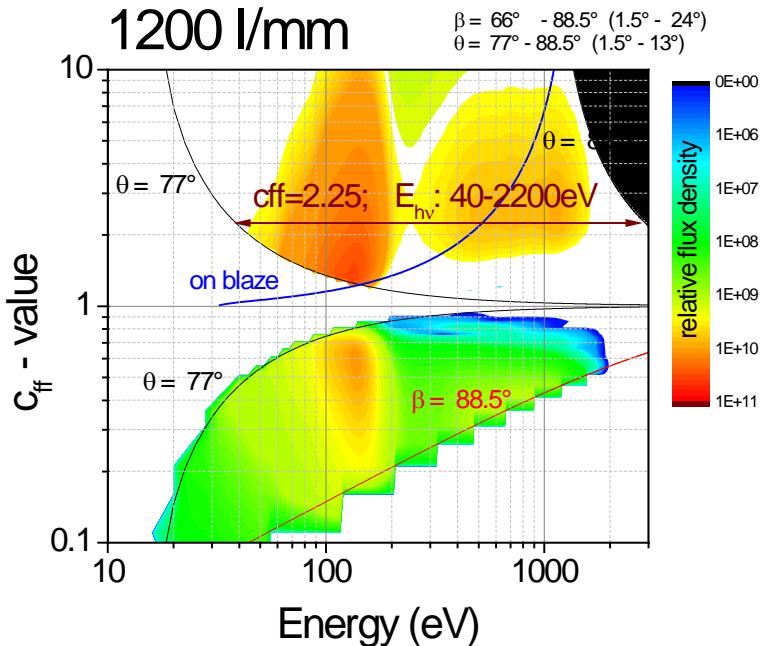
600 l/mm

C_{ff} - value

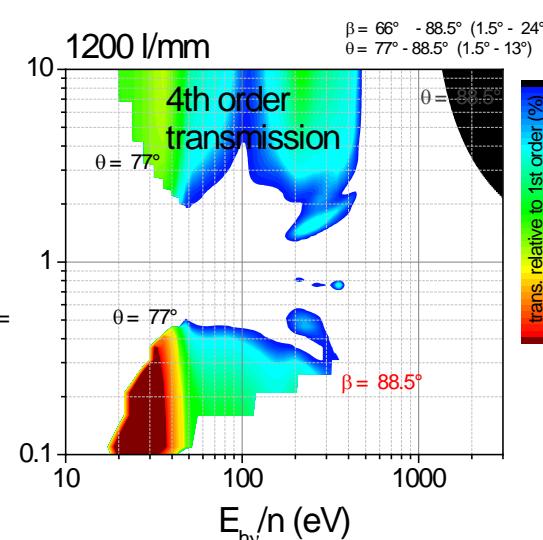
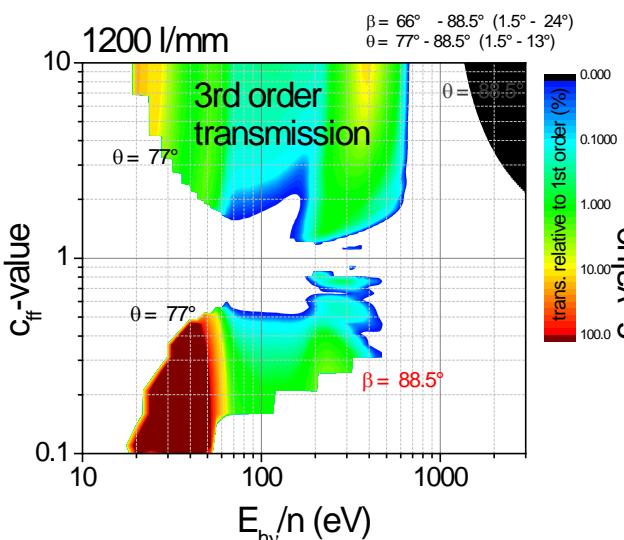
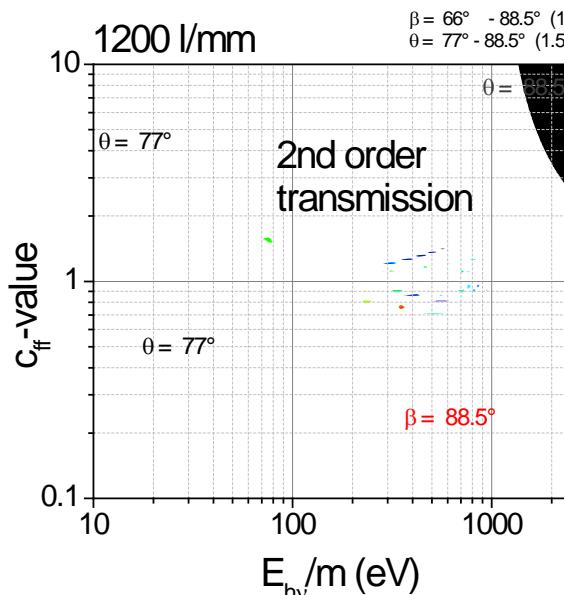
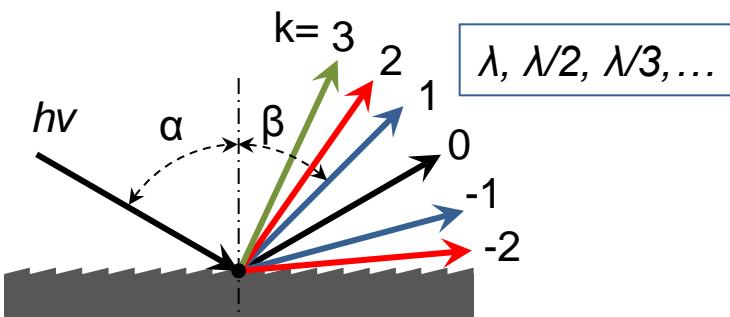


Energy (eV)

Higher order transmission

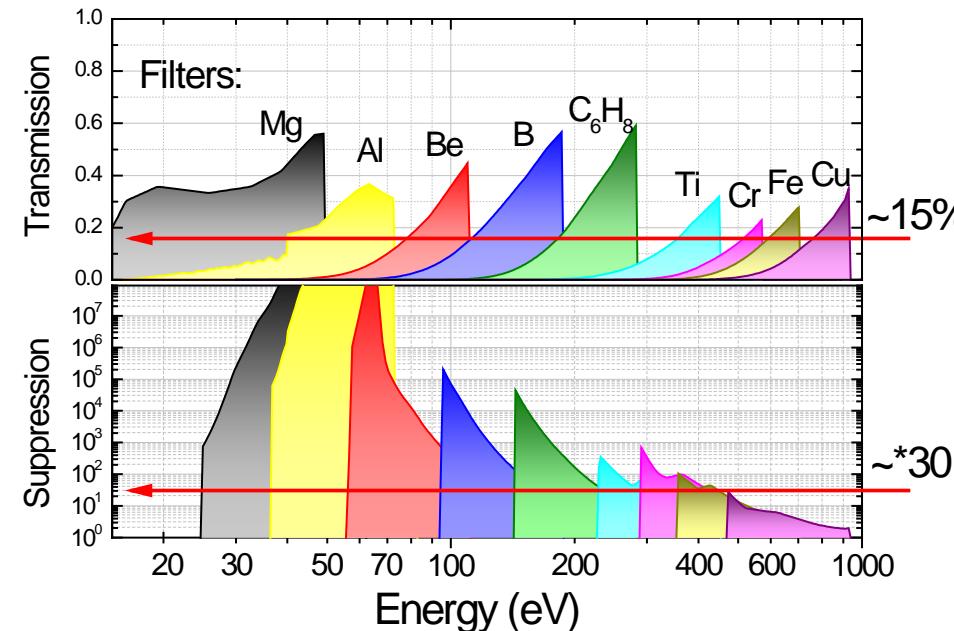


$$Nk\lambda = \sin(\alpha) - \sin(\beta)$$

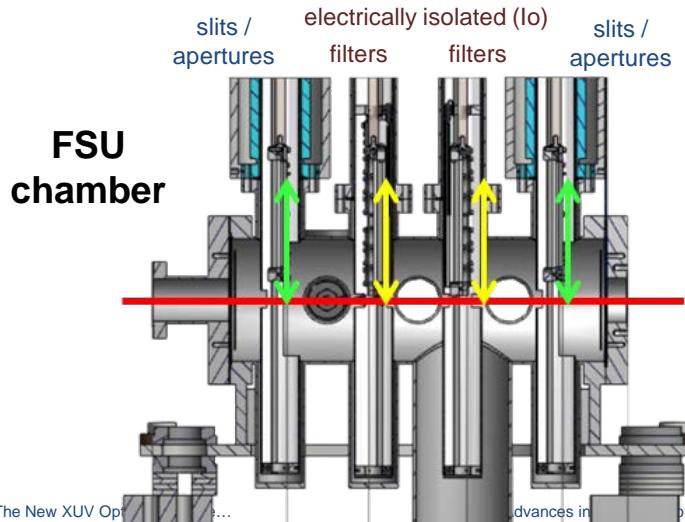
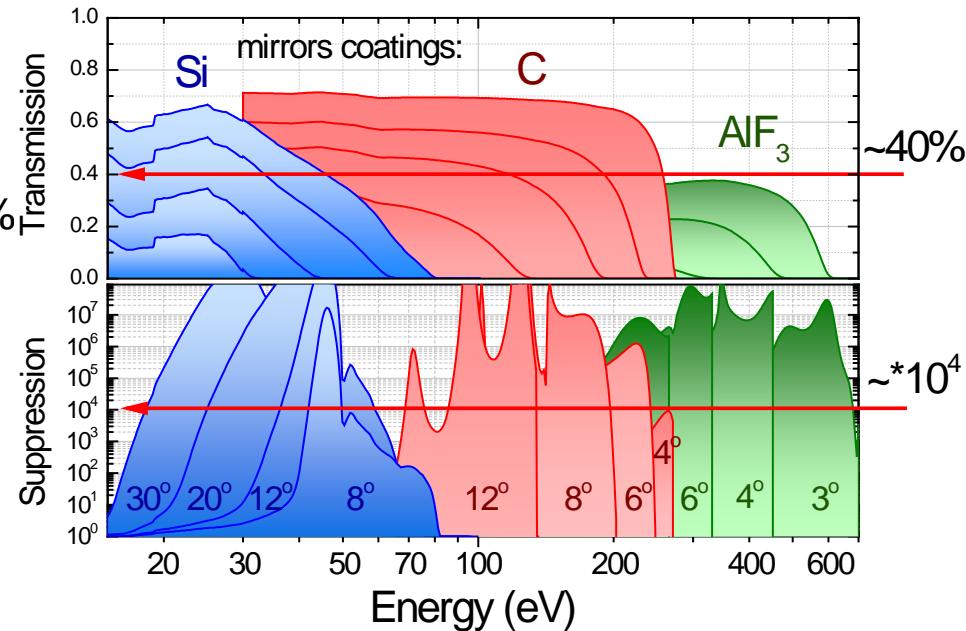


Higher order suppression

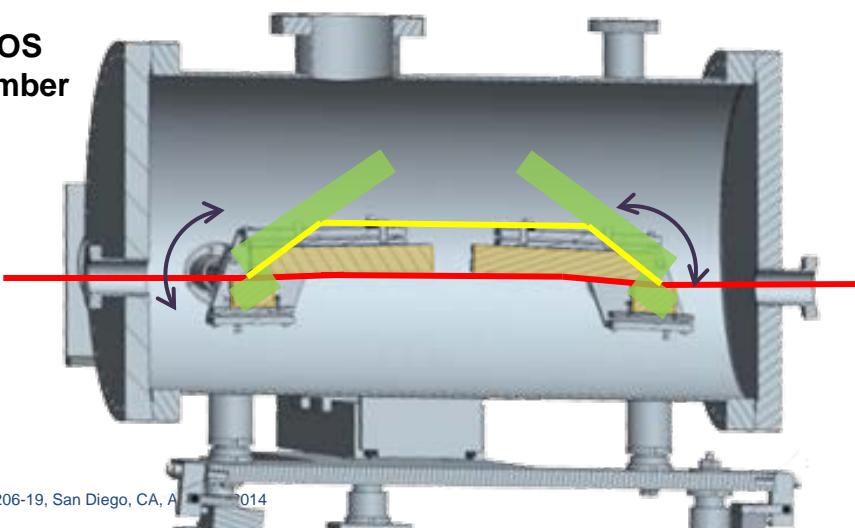
Set of 12 absorption filters



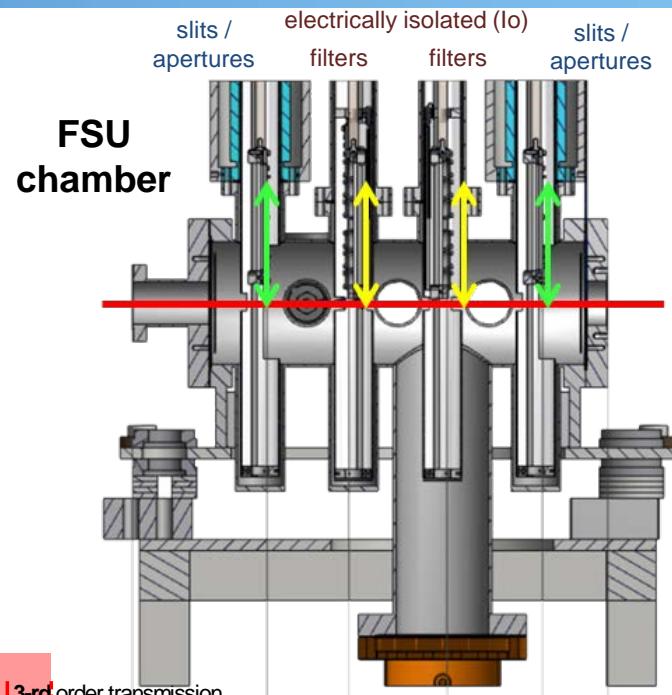
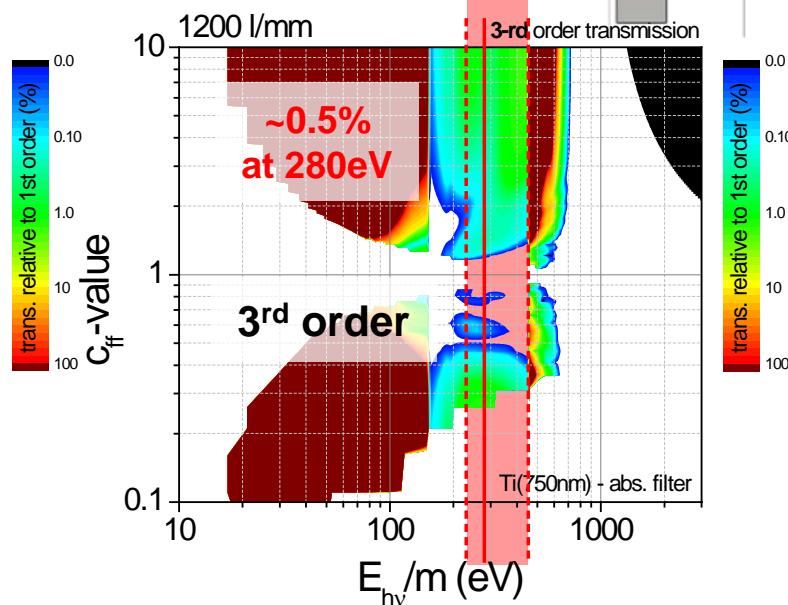
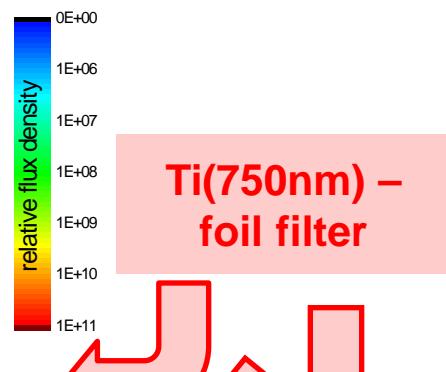
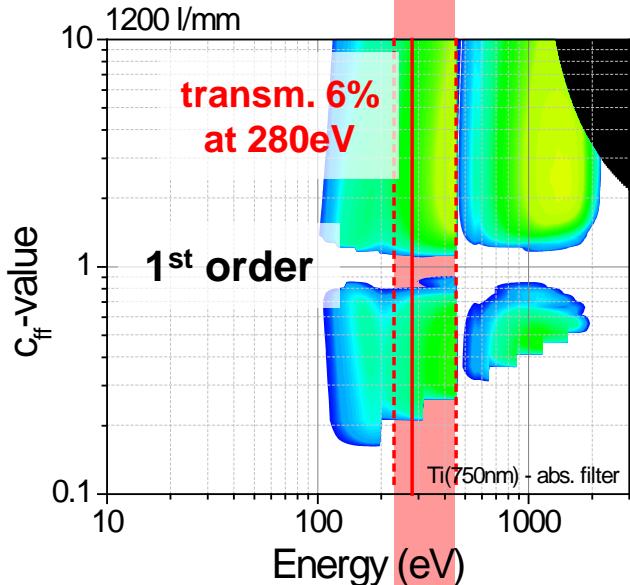
4-mirror system



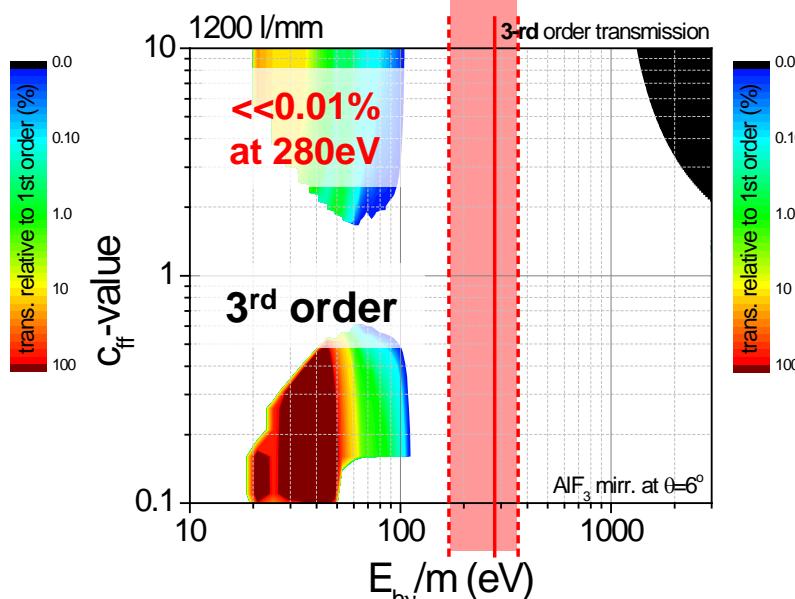
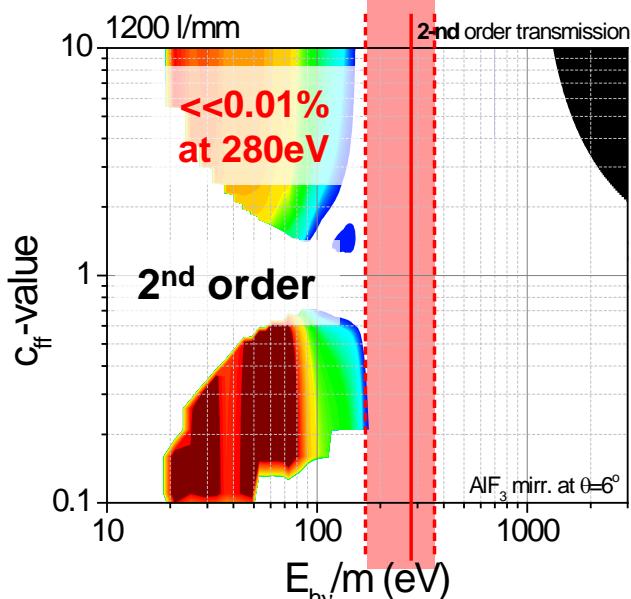
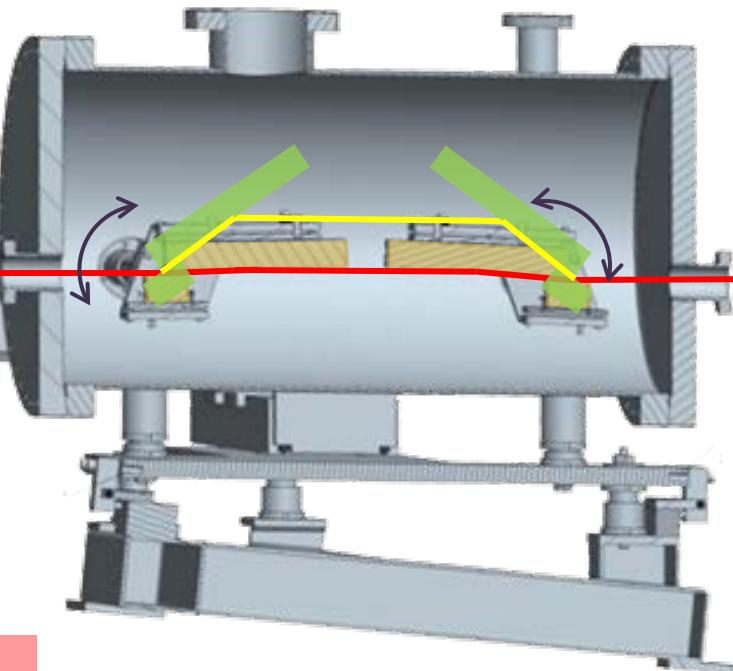
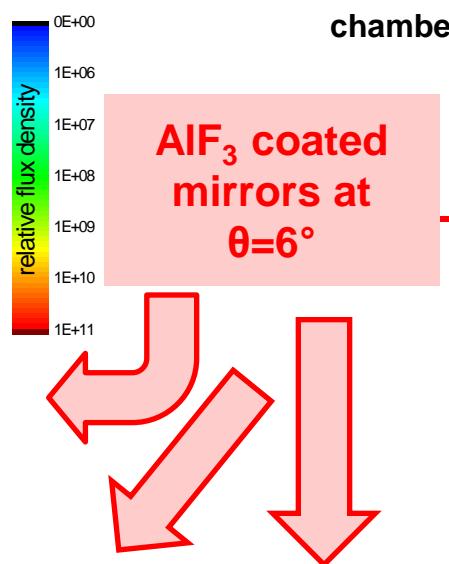
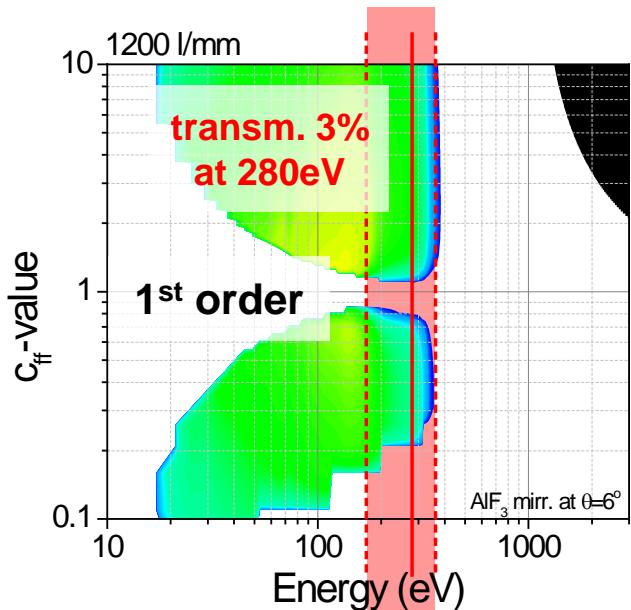
HiOS
chamber



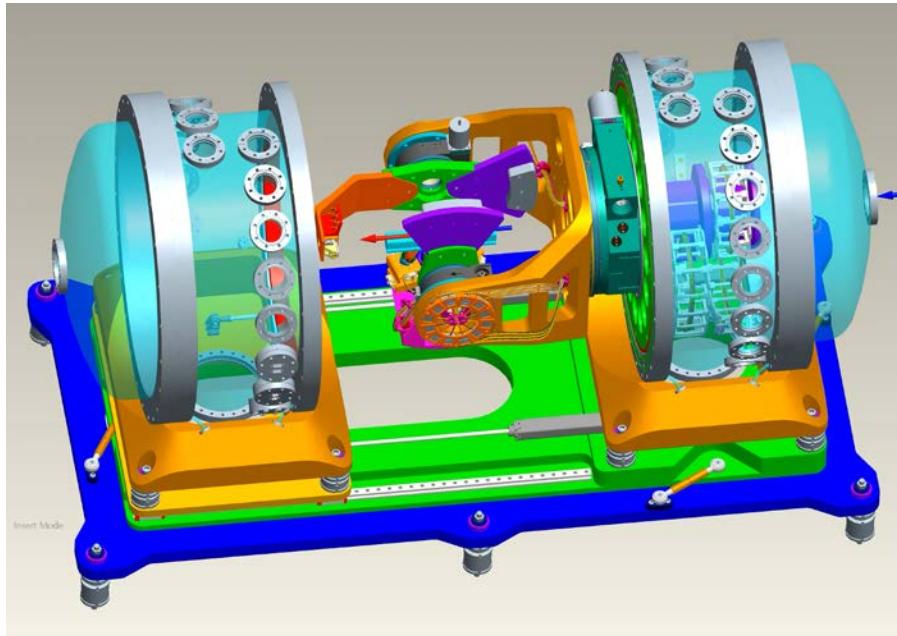
Higher order suppression for 280 eV using Ti - absorption filter



Higher order suppression for 280eV using HiOS

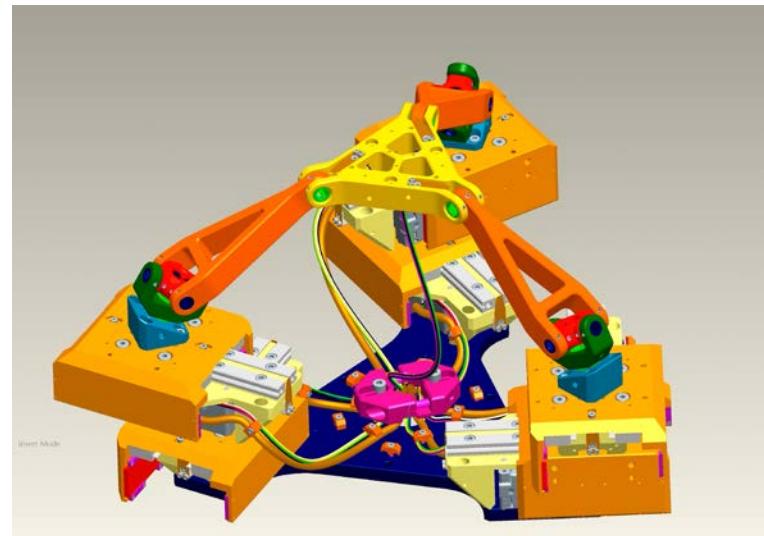


The endstation: Four circle – six axes UHV-Reflectometer



- Azimuthal 360° rotation: Rs and Rp
- Wide angular range: $\theta = 0^\circ - \sim 90^\circ$
- Different detectors: photodiodes, channeltron, Kerr (polarisation), ...
- Load-lock for samples: $< 50 \times 50 \times 10 \text{ mm}^3$

Tripod unit for sample adjustment



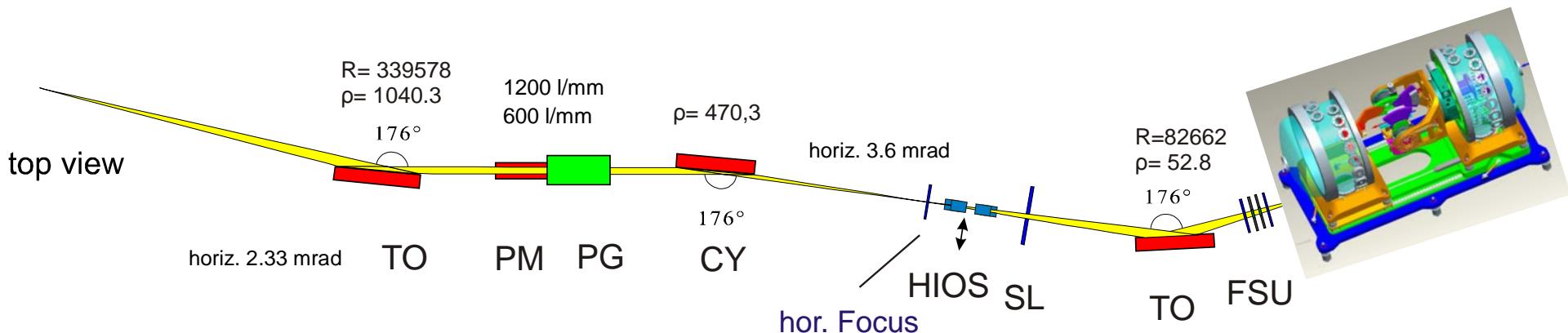
- Six degrees of freedom
- Sample weight: 4 kg
- Sample size: $300 \times 60 \times 60 \text{ mm}^3$
- Motor resolution: 100 nm / 0.001°
- Max. scan range +/- 15 mm

Pointing stability: $10 \mu\text{m} / 0.01^\circ$

Conclusion

- HZB grating production facility is successfully operating
- HZB grating in-situ metrology facility is close to operation
- Attractive XUV Optics Beamline at BESSY-II
- At-wavelength metrology (quality control) of XUV-optics
- Suited for large scale samples
- Measurements at short-term request
- Non-destructive investigation and characterization
- In depth analysis of materials and buried interfaces

The setup will be open for user operation to the end 2014





Thank you for attention!